

In the Claims:

Please amend claims 1, 5, 10, 19 and 20 as follows:

1. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide;
 - an additive for removing the residues comprising a fluoride having a formula $\text{NR}_1\text{R}_2\text{R}_3\text{R}_4\text{F}$, where R_1 , R_2 , R_3 , and R_4 are each independently ~~a hydrogen~~ or an alkyl group; and
 - a co-solvent for dissolving said additive in said CO_2 at a pressurized fluid condition.
2. (Original) The composition of claim 1 wherein the additive further comprises a basic compound.
- 3 - 4. (Canceled).
5. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide,
 - a compound having a hydroxyl group,
 - a fluoride having a formula $\text{NR}_1\text{R}_2\text{R}_3\text{R}_4\text{F}$, where R_1 , R_2 , R_3 , and R_4 are each independently ~~a hydrogen~~ or an alkyl group.
6. (Original) The composition of claim 5 further comprising a basic compound.
7. (Original) The composition of claim 6 wherein the basic compound is selected from a quaternary ammonium hydroxide, an alkylamine, an alkanolamine, a hydroxylamine, and mixtures thereof.
8. (Original) The composition of claim 5 further comprising a co-solvent selected from dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, and mixtures thereof.

9. (Original) The composition of claim 8 wherein the co-solvent comprises deionized water.
10. (Currently Amended) The composition of claim 8 wherein the co-solvent is ~~substantially free of~~ does not include water.
- 11 - 12. (Canceled).
13. (Original) The composition of claim 5 wherein the fluoride is selected from ammonium fluoride, tetramethylammoniumfluoride, tetraethylammoniumfluoride, tetrabutylammoniumfluoride, tetrapropylammoniumfluoride, choline fluoride, and mixtures thereof.
14. (Original) The composition of claim 5 wherein the compound is selected from ethanol, methanol, n-propanol, isopropanol, n-butanol, iso-butanol, diethyleneglycolmonomethylether, diethyleneglycolmonoethylether, hexafluoro-isopropanol, and mixtures thereof.
15. (Canceled)
16. (Currently Amended) The composition of claim 19 wherein the additive is dissolved within the ~~co-solvent~~ co-solvent.
17. (Canceled)
18. (Previously Presented) The composition of claim 19 wherein the residues are at least one selected from photoresist, UV-hardened resist, X-ray hardened resist, ashed resists, carbon-fluorine containing polymer, plasma etch residues, organic process contaminants, and inorganic process contaminants.
19. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:

carbon dioxide wherein the carbon dioxide is in a pressurized or a supercritical fluid state;

an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently ~~a hydrogen or~~ an alkyl group, and mixtures thereof and optionally a basic compound; and

~~a solvent~~ co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, ~~N-methyl-2-pyrrolidone~~ N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof.

20. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
- from 0.001 to 8 weight percent of an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently ~~a hydrogen or~~ an alkyl group, and mixtures thereof and optionally a basic compound;
- from 1 to 50 weight percent of a ~~solvent~~ co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, ~~N-methyl-2-pyrrolidone~~ N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof; and
- carbon dioxide.
21. (Previously Presented) The composition of claim 20 wherein the additive further comprises methane.
22. (Previously Presented) The composition of claim 20 wherein the additive further comprises a surfactant having a CF_x group.

Please add new claim 23 as follows:

23. (New) A composition for removing residues from the microstructure of an object comprising:

carbon dioxide;

an additive for removing the residues comprising a fluoride having a formula $\text{NR}_1\text{R}_2\text{R}_3\text{R}_4\text{F}$, where R_1 , R_2 , R_3 , and R_4 are each independently a hydrogen or an alkyl group, and a quaternary ammonium hydroxide; and

a co-solvent for dissolving said additive in said CO_2 at a pressurized fluid condition.